



# LNQE-Kolloquium

Mittwoch, 19.11.08 um 17:30 - 18:30 Uhr

+ anschließendes Beisammensein

Hörsaal im LfI (Schneiderberg 32, 30167 Hannover, Deutschland)

## *“Nanoimprint lithography for optical components”*

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Optical devices and advanced optical systems exploit more and more the interaction between matter and light at the nanoscale, requiring manufacturing procedure in that range of dimensions with high throughput. First introduced in 1994, nanoimprint lithography (NIL) is a new technique for lithographic patterning of nanostructures, which has advantages of high resolution, high throughput and low cost. This manufacturing technology is presenting great opportunities for innovation and discovery in many engineering and scientific areas, in particular opening the way to nanophotonic components and systems, such as subwavelength gratings, photonic crystals and metamaterials. The area of organic electronics, requiring low cost and high throughput fabrication steps with high resolution, will particularly benefit from this technology.